Improvement of Garfield++ simulation for the gating foil T. Ogawa (SOKENDAI)

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Status in the past 3 years

Simulation side:

- > Prediction of performance
 of the gating foil under higher B.
 (+ understanding of behavior)
- > Simulation did not fit with data under B.
- > Behavior under B is very suspicious.

Comparison of Electron transmission between Exp. and Sim.



Experimental side:

> A method for evaluating transmission has been modified:

Using only an open state data.

Two data set (normal/reverse voltage of Edrift) are not necessary.

http://www-jlc.kek.jp/jlc/sites/default/files/7.27SagaYamashita.pptx

Geometries for the simulation

Smooth trapezoidal

Not smooth

trapezoidal



Geometry parameters Measurement results

"Development of gating foils to inhibit ion feedback using FPC production techniques" Daisuke Arai (presented at MPGD2015)

	Rim width (um)		Copper thickness(um)	
	F-side	B-side	F-side	B-side
Ave.	26.74	30.96	9.20	2.83
Max-Min	6.87	7.27	3.19	0.89
3σ	4.66	5.03	2.33	0.69

Item	Gating foil	
Hole size	304µm	
Hole pitch	335µm	
Rim width : F-side	27µm	
Rim width : B-side	31um	
Insulator thickness	12.5µm	
size	100mm x 100mm	
Processing time	70min (only laser)	
Optical aperture ratio	82.3%	





Simulation

Avalanche Microscopic, with "Null collision steps"

originally implemented in garfield

There is a switch on "Null collision steps"

E-field is updated
in each step after sampling time ∆t
even if the step is null-collision.
According to a developer
this was supposed that
more precise tracking is given.



Simulation: AvalancheMicrosopic

Avalanche Microscopic function,

- 1). An electron trajectory is calculated based on given sampling time Δt (= -< τ > log(u) u[0,1]),
- 2). Electron kinetic energy ε ' after Δt is evaluated

$$\epsilon' = \epsilon + q\mathbf{v} \cdot \mathbf{E}\Delta t + \frac{q^2}{2m_e}\mathbf{E}^2\Delta t^2.$$

A change of the kinetic energy after Δt

 $v \,$ and $E \,$ do not have time dependence, initial information are continuously used $\,$ during Δt

(acceleration and deceleration are not sufficient.)

In reality,

E-field dramatically varies. especially at around geometry. v and E should be time-dependent variables like v(t) and E(r(t)), https://cds.cern.ch/record/1500583/files/CERN-<u>THESIS-2012-208.pdf</u> Heinrich Schindler, Ph.D thesis ``Microscopic Simulation of Particle Detector", CERN-THESIS-2012-208, 13/12/2012

 $p22 \sim p25$



Simulation: AvalancheMicrosopic w/ sub-step

Avalanche Microscopic function,

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$$\epsilon' = \epsilon + q\mathbf{v} \cdot \mathbf{E}\Delta t + \frac{q^2}{2m_e}\mathbf{E}^2\Delta t^2.$$

change of the kinetic energy after Δt

Defined sub-step time \delta t $\delta t (= \Delta t/N)$ recover above First approximation with N=1

$$\epsilon' = \epsilon + \sum_{i}^{N} \underbrace{q \boldsymbol{v}_{i}(\boldsymbol{E}_{i-1}, \delta t_{i})}_{\text{time dependent v}} \cdot \boldsymbol{E}_{i}(\boldsymbol{r}_{i-1}(\delta t_{i-1}))\delta t_{i}$$

$$+ \sum_{i}^{N} \frac{q^{2}}{2m_{e}} \boldsymbol{E}_{i}(\boldsymbol{r}_{i-1}(\delta t_{i-1}))^{2} \delta t_{i}^{2}$$

https://cds.cern.ch/record/1500583/files/CERN-<u>THESIS-2012-208.pdf</u> Heinrich Schindler, Ph.D thesis ``Microscopic Simulation of Particle Detector", CERN-THESIS-2012-208, 13/12/2012

p22 ~ p25

subscripts i, i-1 is not checked carefully

v depends on E and δt E depends on r r depends on δt

A program has to access a field map many times Huge CPU consumption and time is necessary.

If the field map is precisely generated, more time is needed

Simulation: AvalancheMicrosopic w/ sub-step approx.

Avalanche Microscopic function,

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- 2). Electron kinetic energy ε ' after Δt is evaluated

$$\epsilon' = \epsilon + q\mathbf{v} \cdot \mathbf{E}\Delta t + \frac{q^2}{2m_e}\mathbf{E}^2\Delta t^2.$$

change of the kinetic energy after Δt

Defined sub-step time \delta t = \Delta t/N recover above First approximation with N=1

I check E' (v(initial) $* \Delta t$)

$$dE = E - E'$$
initial after Δt

$$\epsilon' = \epsilon + \sum_{i}^{N} q v_i \left(E - \frac{dE}{N} i, \delta t_i \right) \cdot \left(E - \frac{dE}{N} i \right) \delta t_i$$

$$+ \sum_{i}^{N} \frac{q^2}{2m_e} \left(E - \frac{dE}{N} i \right)^2 \delta t_i^2$$

$$dE = E - E'$$

$$Continuously include the variation as the variation as the variation as the variation is linearly changed.$$

$$E - \frac{dE}{N} i$$

$$Under the assumption : the variation of the E-field b/w E(r) and E'(r') (within \Delta t) is linearly changed.$$

https://cds.cern.ch/record/1500583/files/CERN-<u>THESIS-2012-208.pdf</u> Heinrich Schindler, Ph.D thesis ``Microscopic Simulation of Particle Detector", CERN-THESIS-2012-208, 13/12/2012

p22 ~ p25

Simulation w/ sub-step approx.



Simulation w/ sub-step



Another simulation is the closed state

Ion blocking measurement (exp. data is with an electron) \rightarrow The key point is diffusion.



10-3

 10^{-4}

10⁻⁵

-20

-15

- \rightarrow B=0 give enough prediction for the ion blocking,
 - Exp. with the electron. can give the lower limit for the ion blocking
 - The modified version gives similar result (electron)



with Drift Chambers

Textbook

 \oplus Meas. elec. (B=0)

- Diele. 12.5µm / HolePitch 335µm - UpCopp. 9.5µm / LwCopp. 3.0µm

- UpRim. 27µm / LwRim. 31 µm

Volage to the gating GEM [V]

-5

- T2K gas / E-feild 230V/cm

Geometry

-10

Particle Detection

52

0

Summary

Simulation was modified for predictions of the behavior of the gating foil (I need to have discussion with a developer)

The Results reproduce experiment to some extent for 0 and 1 T. With 0-1 V operation the transmission of >80% is PROBABLY achievable under ~3.5/4.0 T.

Simulation indicate that ion blocking of $<10^{-5}$ even for $<10^{-6}$ is PROBABLY achievable for a higher B field with the applied voltage of < -20V.

Remaining tasks are 1). direct measurement of ion blocking using the ion itself. and compare with the simulation (confirmation).

2). actual measurement under the higher B field. (electron/ion)

Ratio reaching to the dielectric



Ratio reaching to a lower copper







